## IPstrong, version 1.1 inputs

- Nominal bunch charge and beam energy
- Energy spread configurable
- New beamstrahlung input needed ?
- Misalignments can be introduced (μm)
- o laser spot considerably smaller (10  $\mu$ m<sup>2</sup> rather than 100  $\mu$ m<sup>2</sup>)
- mCP possible, but not produced if the process is turned off

## JETI40 parameter file

```
rotang, 17.2
                                   # crossing angle (degrees). zero is head on
bunchcha, 1,5d9
                                     # number of particles in the bunch
nToTMeshPts.20.20.1000
                                   # monte carlo mesh units. The z value is imp
Ene. 16.5d9
                                   # beam energy (GeV)
EneSpread, 0.01
                                   # beam energy spread (fraction)
pdg.11
                                   # pdg number of first particle bunch
sigxyz.5d3.5d3.24d3
                                   # bunch size in sigma xvz (nm)
                                   # emittance (mm mrad)
emitxy, 1.4, 1.4
msalqn,00.0d0
                                  # misalignment of the two beams (nm)
inpname."data lxphotons w001x0 emittance14 f5m xyze rndm sim88106 1 6.txt"
w0.1.78d3
                                   # strong laser (half) spot size (nm)
ICSpeaksep, 10.0d3
                                   # for donut and twin peak intense laser fiel
pulseshape, gauss
                                  # gauss, flat, flatTR (flat transverse and lo
laslam,800.0d0
                                   # strong laser wavelength (nm)
laspuls.25d-15
                                   # strong laser pulse length (s)
Enelas.0.8
                                   # strong laser energy (Joules)
seedlam, 41.79d0
                                   # probe laser, if present
seedlaspuls.5d-13
                                   # seed laser pulse length (s)
seedEnelas.2.0d-10
                                   # seed laser energy (Joules)
focusfield,0.0d0
                                   # longitudinal focussing magnetic field
MCPmass, 0.002
                                     # milli-charged particle mass (units of el
MCPcharge.0.0001
                                   # milli-charged particle charge (units of el
bunchnum.1.0
                             # t op=le7 * 0.4 efficiency
hicson,1
                                   # switch for HICS process
opppon,1
                                   # switch for OPPP process
oppprealon.1
                                   # OPPP process produces real particles (not
scson.0
                                   # switch for second order SCS process
beamstron,0
                                   # switch for beamstrahlung in charged bunch
felon,0
                                   # optical FEL switch, intensity of strong la
```

# milli-charged particle switch

mcpon.0

## IPstrong, version comparison

- Compare previous and new IPstrong versions
- Benchmark point: pure OPPP, initial gammas
- $1.3 \times 10^{8}$ . 7 GeV
- o gather positrons over N=10 bunches
- same no. positrons within statistical error
- Positron spectrum needs further validation

## OPPP positrons per bunch

